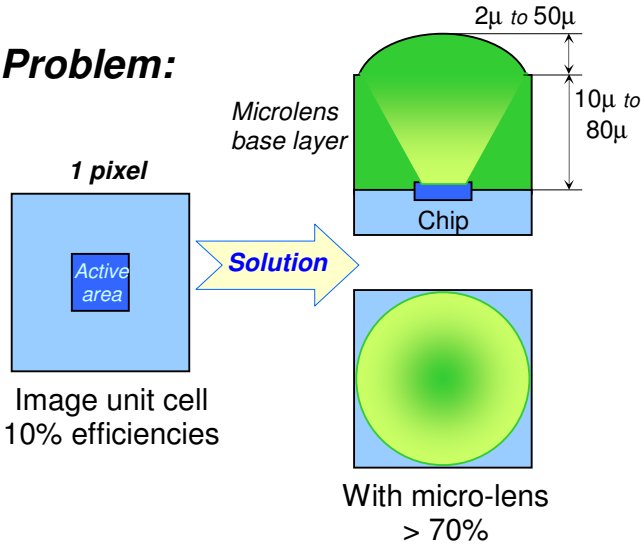


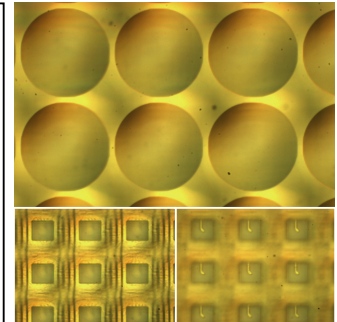
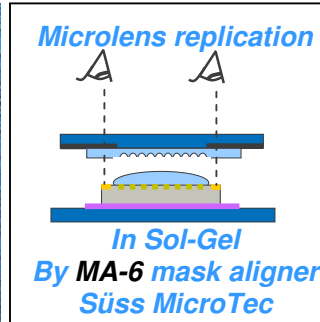
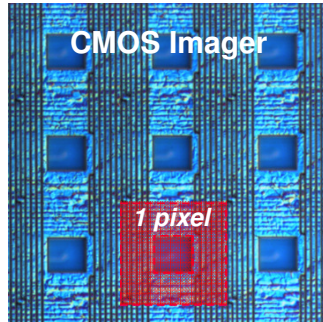
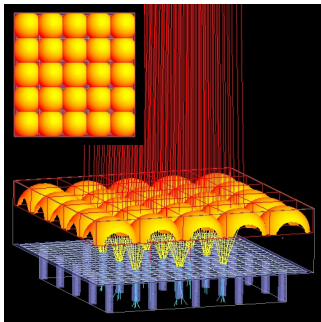
Fill Factor Enhancement for CMOS – IMAGER

Problem:



Customized Solution:

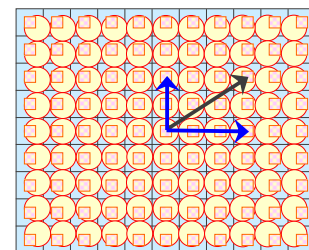
- Consulting
- Optical design
- Microlens manufacturing
- Aligned replication
- Characterization



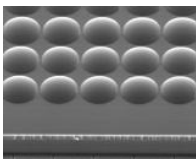
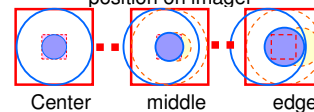
Special:

Aberration correction (telecentric error) by local displacement

- Microlens array lateral accuracy < 1μ
- Microlens positioning accuracy and height $\sim 2\mu$
- Mask design << 250 nm



Microlens displacement by pixel position on imager



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